





Electrical Engineering, Photonic Integration

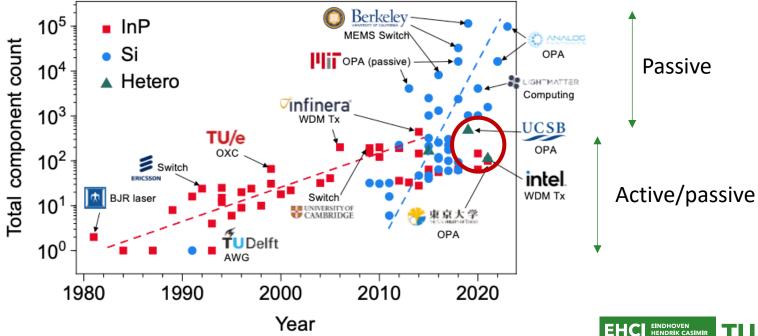
#### **Outline**

- Density bottleneck in photonic integrated circuits
- Our technology on an InP membrane
- Miniaturization and efficiency boost in active devices
- Summary



## **Photonic Integration**

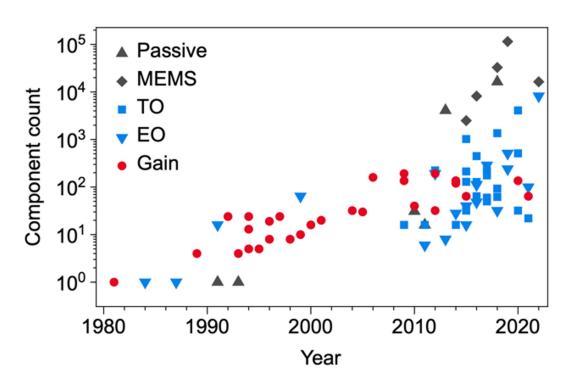
- Density bottleneck is not solved by introducing Si photonics alone
- Active components limit the density in heterogeneous circuits







#### **Photonic Integration**

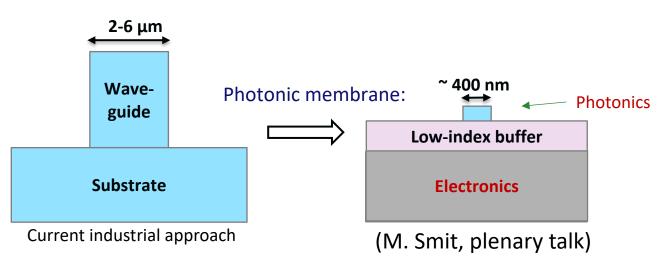


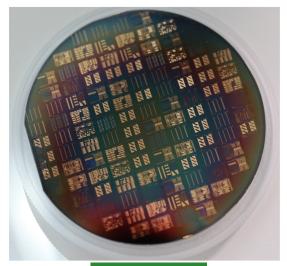
- Density boost driven by passives and MEMS optics
- Gain and EO elements remained relatively bulky



## **Photonic Integration in a membrane**

- InP membrane: InP amplifiers/lasers + SiPh-like nanowire waveguides
- Wafer-scale assembly with electronics

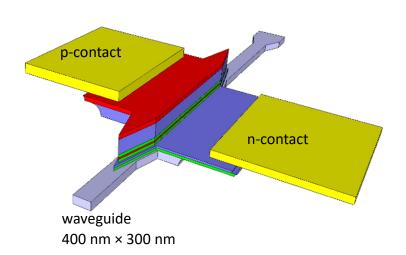


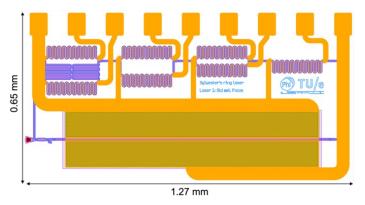




#### Lasers on nanophotonic waveguides

- S-shaped amplifier/laser for balanced confinement vs power handling
- Improve optical mode matching very short tapers
- No critical alignment (lithography overlay accuracy)

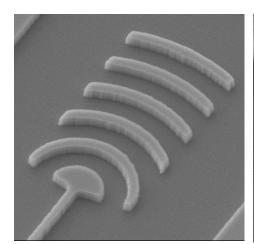




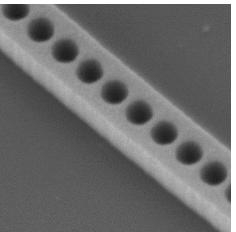
Example Compact tunable laser on membrane This Session @ 15:15 – 15:30



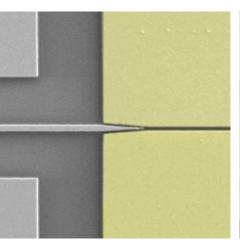
## Nanophotonic passive library



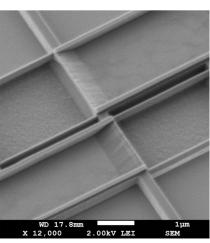
Grating antenna



Photonic crystal



**Plasmonics** 



Polarization rotator

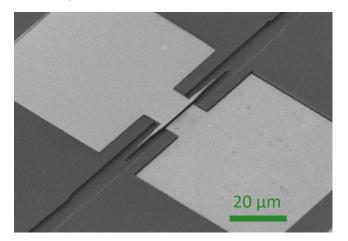
TE/TM conversion in 4 μm length This Session @ 15:00 – 15:15

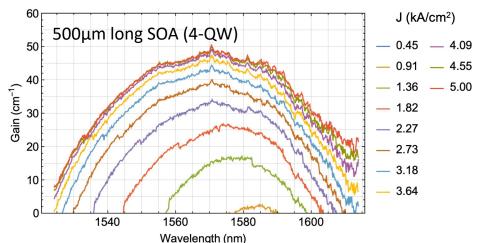


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## Amplifiers are intrinsically power hungry

- ~ 200 dB/cm net modal gain in 4-QW SOAs
- Wall-plug efficiency (WPE) typically < 1%</li>
- High electrical power supply to amplifier weak optical signals
- Improvements exist at device level: optimizing QW materials, electrical structure, etc.



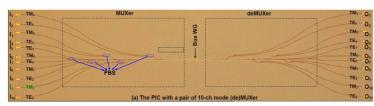




#### Circuit-level method: Folding the device by MDM

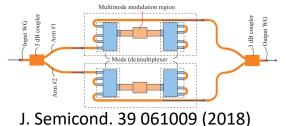
- Non-resonant light recirculation has been used to boost efficiency in linear phase shifters
- Thermo-optic phase shifter





Laser & Photon. Rev. **12**, 1700109 (2018)

Electro-optic phase shifters,







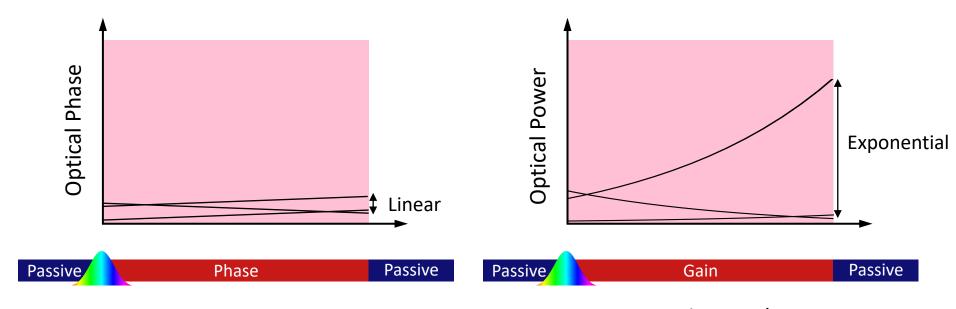
APL Photonics 7, 106102 (2022)

Communications Physics 6: 17 (2023)

Its use in nonlinear devices (SOAs, EAMs) is not studied: investigated for first time in this work



# Multi-pass: linear vs nonlinear



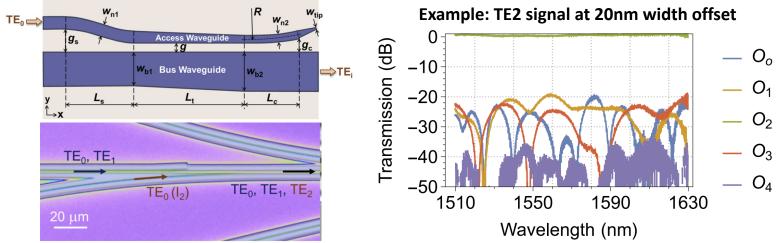
N-pass: N times enhancement

N-pass: >> N times enhancement



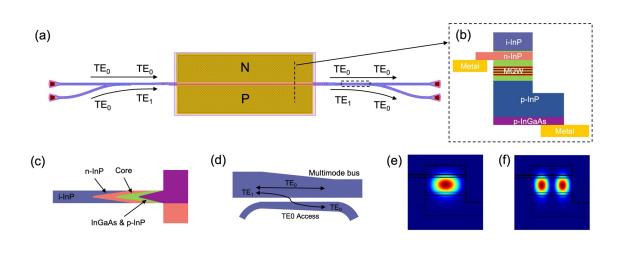
## Fab tolerant mode (de)multiplexers in InP membrane

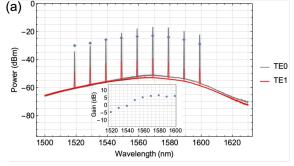
- First mode multiplxer (5 modes) on InP
- Broadband (~ 100nm)
- EL < 1 dB, XT < -14 dB with 50nm width variation
- InP offers high fab tolerance due to moderate index contrast

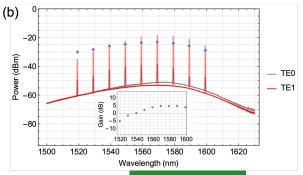


### Mode multiplexing in membrane SOAs

- Combining mode multiplexers and amplifiers made possible InP membrane technology
- TE<sub>1</sub> experiences slightly lower gain than TE<sub>0</sub>



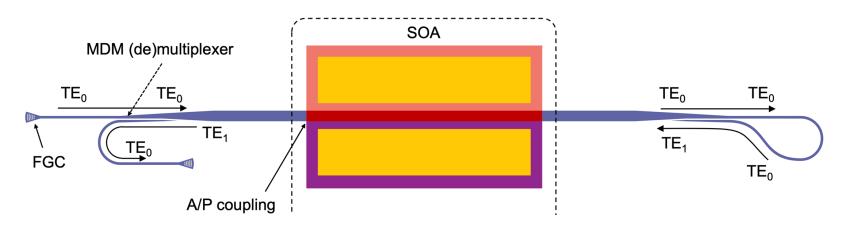






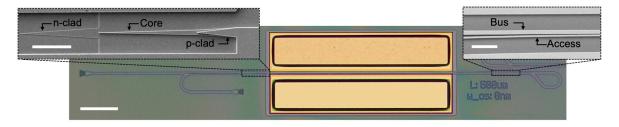
Non-resonant 2-pass SOAs based on mode multiplexing (patent pending):

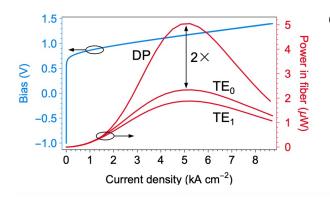
- Low-crosstalk in the MDM coupler suppresses resonance;
- Gain boosted without increase in pump current, and/or
- "Halved" footprint and pumped energy for the same gain.

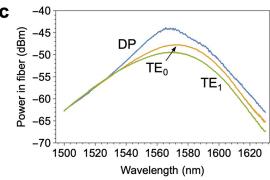




2-pass amplified spontaneous emission:





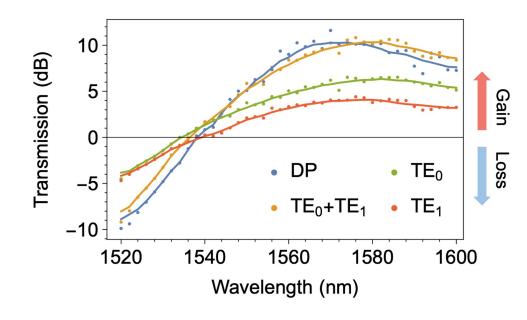




arXiv:2303.07485 presented in CLEO 2023

2-pass net modal gain (500um long SOA at 4.1 kA/cm<sup>2</sup>):

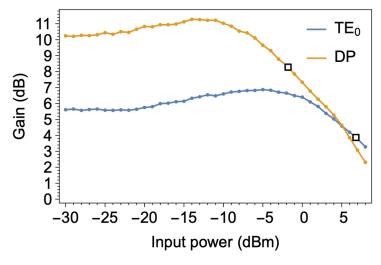
- Gain boosted from 6.2 dB for single pass to 11.6 dB (87% enhancement)
- Absorption (as EAM) also boosted as seen in 1520-1540nm region
- Universal circuit-level method applicable to any PIC platform

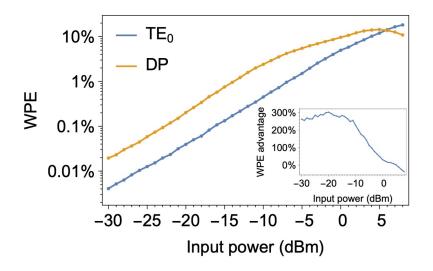


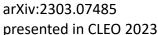


Saturation is earlier for 2-pass than 1-pass;

Significant advantage for low input powers (which is the case for most telecom, datacom and switching applications): Wall-plug efficiency (>300% enhancement)







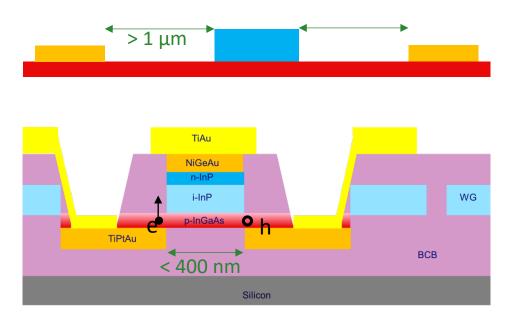


## >110 GHz photodiode

Conventional design

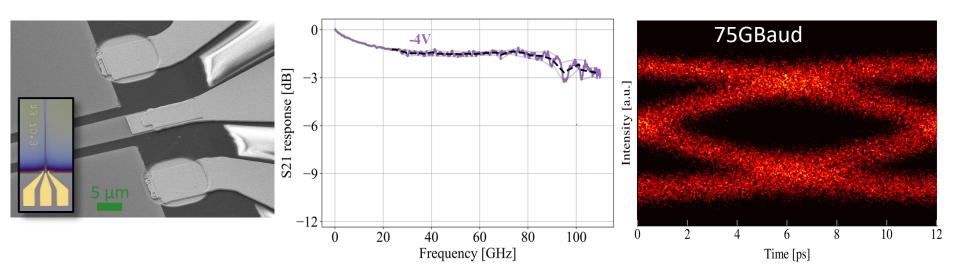
Our design

Closer metal contacts without loss compromise





#### >110 GHz photodiode

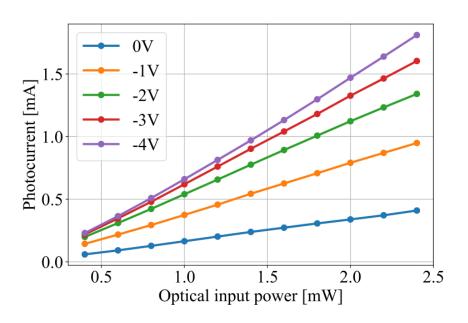


Micron-square footprint: 5 x 2 micron<sup>2</sup>

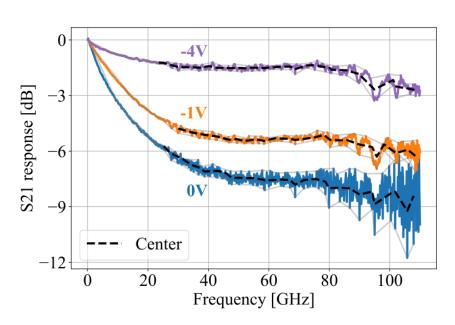
InP membrane platform for density and speed scaling



## >110 GHz photodiode



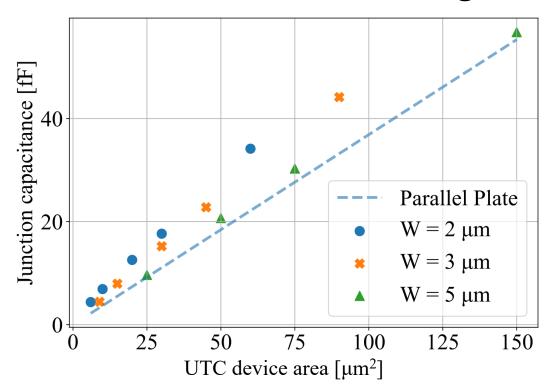
0.6 - 0.7 A/W responsivity 5 x 2 micron<sup>2</sup> photodiode area



No band-smoothing layers in this device; resolved in a parallel work



## **Carrier diffusion limited design**



Deviation from parallel plate model for 2 & 3 µm wide devices may be caused by a parasitic capacitance

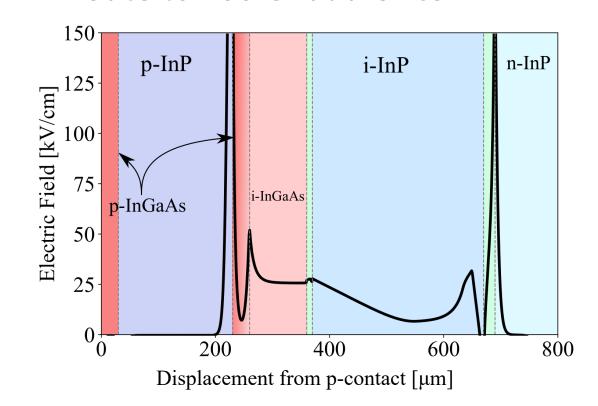
Leakage of the electric field around the edges of the structure.

Junction capacitance as low as 4.4 fF is achieved

Series resistance of the same device of  $6.5~\Omega$ 



#### **Route to 200 GBaud UTCs**



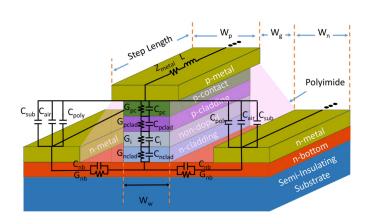
Transit time further reduced by separating the absorption layer into an undoped and p-doped region

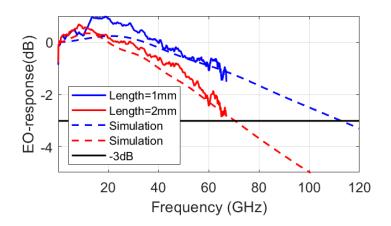
Graded doping to ensure electron overshoot velocity is reached

The simulated electric field profile at -0.5 V bias and at 1 mA sufficiently high to ensure overshoot velocity.



## **High-density 100GHz-class EO modulators**





Demonstrated on semi-insulating InP substrate, but transferrable to membrane

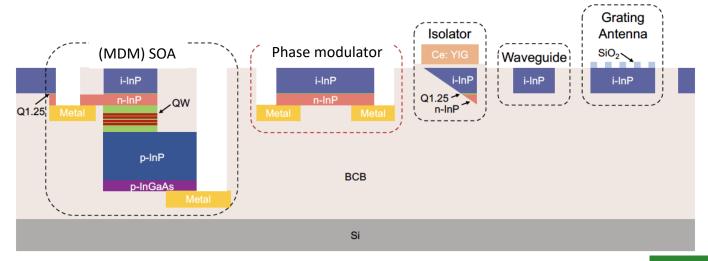
For details please attend:

Next session in this room @ 17:00 - 17:15



## Laser and nanophotonics in one process flow

- An active-passive platform realized with a single process flow
- Eliminate the need of assembly or bonding for external light source





#### Summary

- Active-passive photonic integration on an InP membrane
- InP membrane nanophotonics enables compact and highly efficient gain and EO devices
- Circuit-level method widely applicable to any PIC platform











